

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Young Hoon PARK, et al.)
Serial No.: 10/511,883) Group Art Unit: 1763
Filed: October 19, 2004) Examiner:
For: APPARATUS AND METHOD FOR) NG, James Wai Heung
DEPOSITING THIN FILM ON WAFER)
USING REMOTE PLASMA)

**REPLY TO NON-FINAL OFFICE ACTION
UNDER 37 CFR 1.111, WITH AMENDMENT**

VIA EFS
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed January 10, 2008, Applicants request reconsideration in view of the following amendments and remarks for entry in the above-identified application.

Amendments to the Claims begin on page 2 of this paper; and

Remarks begin on page 8 of this paper.